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Patent. *IFW*

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application for:

Krishna Parat et al.

Application No.: 10/669,825

Filed: September 23, 2003

For: DUAL TRENCH ISOLATION  
USING SINGLE CRITICAL  
LITHOGRAPHIC PATTERNING

Examiner: Kilday, Lisa A.

Art Group: 2829

CERTIFICATE OF MAILING

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Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313

AMENDMENT AND RESPONSE

Dear Sir:

This communication is being submitted in response to the Office Action mailed on **September 8, 2004**. Reconsideration of the captioned application, in light of the following amendments and remarks is respectfully requested.

**Amendments to the Claims** are reflected in the listing of claims that begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.

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